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	APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
	10/735,815	12/16/2003	Naruhiko Kaji	402913/TAKADA	2866
	23548 75	590 01/27/2005		EXAM	INER
	LEYDIG VOIT & MAYER, LTD 700 THIRTEENTH ST. NW SUITE 300 WASHINGTON, DC 20005-3960			LOKE, STEVEN HO YIN	
				ART UNIT	PAPER NUMBER
				2811	
				DATE MAILED: 01/27/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

<u> </u>				70		
		Application No.	Applicant(s)			
		10/735,815	735,815 KAJI, NARUHIKO			
	Office Action Summary	Examin r	Art Unit			
		Steven Loke	2811			
Period fo	Th MAILING DATE of this communication apport Reply	pears on the cov r sh t with th	correspond nc address	-		
THE - Exte after - If the - If NC - Failt Any	ORTENED STATUTORY PERIOD FOR REPL MAILING DATE OF THIS COMMUNICATION. nsions of time may be available under the provisions of 37 CFR 1.1 SIX (6) MONTHS from the mailing date of this communication. e period for reply specified above is less than thirty (30) days, a repl period for reply is specified above, the maximum statutory period ure to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be tin y within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from , cause the application to become ABANDONE	nety filed  rs will be considered timety.  I the mailing date of this communication.  D (35 U.S.C. § 133).			
Status						
1)🖂	Responsive to communication(s) filed on 16 D	ecember 2003 and 15 December	<u> 2004</u> .			
2a) <u></u> □	This action is FINAL. 2b)⊠ This	action is non-final.				
3)	Since this application is in condition for allowa	nce except for formal matters, pro	osecution as to the merits is			
•	closed in accordance with the practice under E	Ex parte Quayle, 1935 C.D. 11, 45	53 O.G. 213.			
Disposit	ion of Claims					
4)⊠	Claim(s) 1-6 is/are pending in the application.					
	4a) Of the above claim(s) 4-6 is/are withdrawn	from consideration.				
5)	Claim(s) is/are allowed.					
6)⊠	Claim(s) <u>1-3</u> is/are rejected.					
7)	Claim(s) is/are objected to.			•		
8)	Claim(s) are subject to restriction and/o	r election requirement.				
Applicat	ion Papers					
9)[	The specification is objected to by the Examine	er.	•			
10)	10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.					
	Applicant may not request that any objection to the	drawing(s) be held in abeyance. See	e 37 CFR 1.85(a).			
	Replacement drawing sheet(s) including the correct	tion is required if the drawing(s) is ob	jected to. See 37 CFR 1.121(d).			
11)	The oath or declaration is objected to by the Ex	kaminer. Note the attached Office	Action or form PTO-152.			
Priority (	under 35 U.S.C. § 119					
12)🛛	Acknowledgment is made of a claim for foreign	priority under 35 U.S.C. § 119(a)	)-(d) or (f).			
a)	☑ All b)☐ Some * c)☐ None of:					
	1. Certified copies of the priority document	s have been received.				
	2. Certified copies of the priority document	s have been received in Applicati	on No			
	3. Copies of the certified copies of the prio	rity documents have been receive	ed in this National Stage			
	application from the International Burea	` ' ''				
* \$	See the attached detailed Office action for a list	of the certified copies not receive	ed.			
Attachmen	t(s)					
1) 🛛 Notic	e of References Cited (PTO-892)	4) 🔲 Interview Summary				
	e of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08)	Paper No(s)/Mail Da	ate Patent Application (PTO-152)			
	mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) or No(s)/Mail Date <u>12/16/03</u> .	6) Other:	acon Appropriation (F 10-102)			

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1. Applicant's election without traverse of claims 1-3 in the reply filed on 12/15/04 is acknowledged.

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- 2. Claims 4-6 are withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected invention, there being no allowable generic or linking claim. Election was made without traverse in the reply filed on 12/15/04.
- 3. Claim 3 is objected to because of the following informalities: line 3, the phrases MSQ and HSQ should be in full written form. Appropriate correction is required.
- 4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

5. Claim 1 is rejected under 35 U.S.C. 102(e) as being clearly anticipated by Vanhaelemeersch et al.

In regards to claim 1, Vanhaelemeersch et al. show all the elements of claimed invention (col. 7, line 53 to col. 8, line 54). It is a semiconductor device (a device formed by the process in Vanhaelemeersch et al.), comprising: a porous dielectric film (insulating layer) on a substance (substrate); an opening portion for wiring (conductive material) in the porous dielectric film; dielectric films (hydrogenated SiOC) covering only side surfaces of the opening portion, each of the dielectric films having a dielectric

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constant not exceeding 3 (k ~ 2.8, see Choi); and a wiring (conductive material) in the opening portion on the dielectric films.

The insulting layer is considered as a low-k dielectric film because any insulating layer can be considered as a low-k dielectric film. There is no boundary for the dielectric constant, k.

- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 7. Claims 2 and 3 are rejected under 35 U.S.C. 103(a) as being unpatentable over Vanhaelemeersch et al.

In regards to claim 2, Vanhaelemeersch et al. differ from the claimed invention by not showing the dielectric films include a fluorinated polyarylene film or an amorphous carbon fluoride. It would have been obvious for the dielectric films include a fluorinated polyarylene film or an amorphous carbon fluoride, since it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability for the intended use. In re Leshin, 125 USPQ 416.

In regards to claim 3, Vanhaelemeersch et al. differ from the claimed invention by not showing the porous low-k dielectric film is selected from the group consisting of a porous MSQ, a porous HSQ, a hybrid film containing both methyl and hydroxyl groups, and a porous organic film containing carbon as a major component. It would have been obvious for the porous low-k dielectric film is selected from the group consisting of a

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porous MSQ, a porous HSQ, a hybrid film containing both methyl and hydroxyl groups, and a porous organic film containing carbon as a major component, since it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability for the intended use. In re Leshin, 125 USPQ 416.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Steven Loke whose telephone number is (571) 272-1657. The examiner can normally be reached on 7:50 am to 5:20 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Eddie Lee can be reached on (571) 272-1732. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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